

# EUROPEAN PATENT OFFICE

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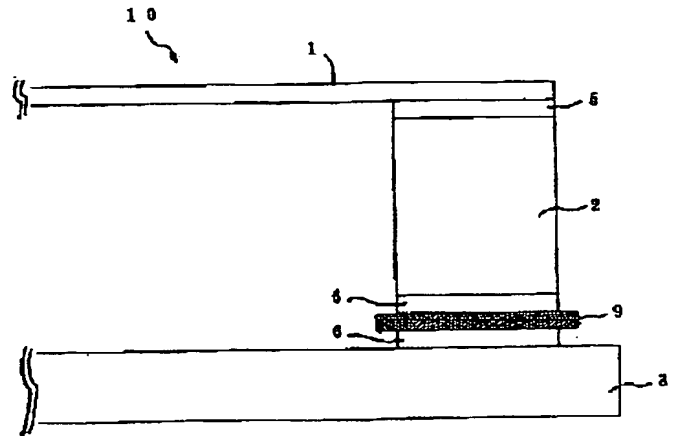
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APPLICANT : SHIN ETSU CHEM CO LTD;

INVENTOR : KASHIDA SHU;

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TITLE : PELLICLE FOR LITHOGRAPHY



**ABSTRACT :** PROBLEM TO BE SOLVED: To prevent production of dust and to avoid such problems that a pellicle film expands and break even when environmental conditions such as external air or temp. change by providing an adhesive layer with an aeration filter to adhere and fix a pellicle to an exposure master plate.

**SOLUTION:** This pellicle consists of a pellicle film 1, frame 2, and adhesive layer 6 in such a manner that the pellicle film 1 is adhered to the upper face of the frame 2 with an adhesive 5 or a good solvent of the pellicle film 1, that the adhesive layer 6 is formed on the lower face of the frame 2 and that the frame is adhered and fixed to an exposure master plate 3. The adhesion layer 6 is provided with an aeration filter 9 so that air can be passed between the inside and outside of the pellicle. Thereby, a sealed state in the frame 2 can be avoided and such a problem that the pellicle film 1 expands or sinks is avoided even when environmental conditions, especially the atmospheric pressure or temp. change.

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